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# Surface chemical analysis — Secondary-ion mass spectrometry — Determination of boron atomic concentration in silicon using uniformly doped materials

*Analyse chimique des surfaces — Spectrométrie de masse des ions secondaires — Dosage des atomes de bore dans le silicium à l'aide de matériaux dopés uniformément*

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Case postale 56 • CH-1211 Geneva 20
Tel. + 41 22 749 01 11
Fax + 41 22 749 09 47
E-mail copyright@iso.org
Web www.iso.org

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